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PATENT Atty. Dkt. ZIMR/0044

Please amend page 7, paragraph 4 as follows:

The present invention also refers to a charged particle beam device according to elaim 21 which includes a charged particle beam source and a focusing lens. The charged particle beam device with the focusing lens according to any one of the claims 1 to 26 is capable of inspecting or structuring a specimen at landing angles that deviate from 90 degrees with high spatial resolution.

Please amend page 8, paragraph 3 as follows:

The present invention also refers to a method of inspecting or structuring a specimen according to claim 26. According to claim 26, the method of inspecting or structuring a specimen by means of a charged particle beam which includes the steps of providing a charged particle beam device having a correcting electrode; inspecting or structuring the specimen at a first landing angle at a first correcting electrode voltage applied to the correcting electrode; and inspecting or structuring the specimen at a second landing angle at a second correcting electrode voltage applied to the correcting electrode.

Please amend page 10, paragraph 3 as follows:

The present invention also refers to a method of inspecting or structuring a specimen according to claim 27. According to claim 27, the method of inspecting or structuring a specimen by means of a charged particle beam which includes the steps of providing a charged particle beam device having at least a first electrode and a correcting electrode; inspecting or structuring the specimen at a first landing angle with the correcting electrode at a first position with respect to the at least first electrode; and inspecting or structuring the specimen at a second landing angle with the correcting electrode at a second position with respect to the at least first electrode.

CH 9/23/09